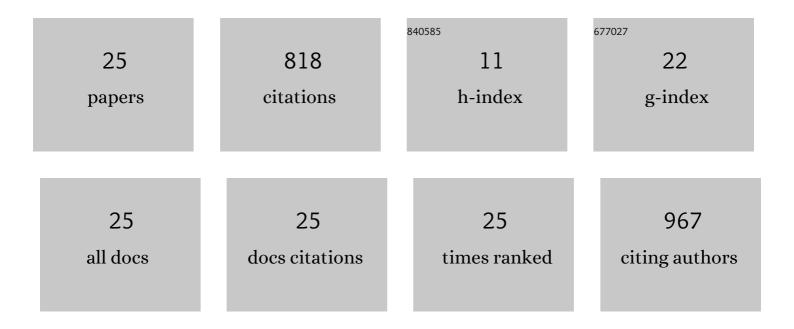
Pavel Baroch

List of Publications by Year in descending order

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#	Article	IF	CITATIONS
1	Tungsten Oxide Based Hydrogen Gas Sensor Prepared by Advanced Magnetron Sputtering. Engineering Proceedings, 2021, 6, .	0.4	0
2	Tuning Stoichiometry and Structure of Pd-WO3â^'x Thin Films for Hydrogen Gas Sensing by High-Power Impulse Magnetron Sputtering. Materials, 2020, 13, 5101.	1.3	3
3	Enhancement of the deposition rate in reactive mid-frequency ac magnetron sputtering of hard and optically transparent ZrO 2 films. Surface and Coatings Technology, 2018, 336, 54-60.	2.2	12
4	In-Ga-Zn-O thin films with tunable optical and electrical properties prepared by high-power impulse magnetron sputtering. Thin Solid Films, 2018, 658, 27-32.	0.8	8
5	Hard Nanocomposite Coatings. , 2014, , 325-353.		19
6	High-rate pulsed reactive magnetron sputtering of oxide nanocomposite coatings. Vacuum, 2013, 87, 96-102.	1.6	26
7	Rapid Sterilization of Escherichia coli by Solution Plasma Process. Japanese Journal of Applied Physics, 2012, 51, 126201.	0.8	7
8	High sensitive detection of volatile organic compounds using superhydrophobic quartz crystal microbalance. Sensors and Actuators B: Chemical, 2012, 164, 15-21.	4.0	41
9	Generation of plasmas in water: utilization of a high-frequency, low-voltage bipolar pulse power supply with impedance control. Plasma Sources Science and Technology, 2011, 20, 034017.	1.3	10
10	Elimination of Arcing in Reactive Sputtering of Al ₂ O ₃ Thin Films Prepared by DC Pulse Single Magnetron. Plasma Processes and Polymers, 2011, 8, 500-504.	1.6	7
11	Creating Biointerface on Polymer by Plasma-Initiated Graft Polymerization. Transactions of the Materials Research Society of Japan, 2011, 36, 549-552.	0.2	2
12	High-rate reactive deposition of transparent SiO2 films containing low amount of Zr from molten magnetron target. Thin Solid Films, 2010, 519, 775-777.	0.8	32
13	Two-Functional Direct Current Sputtered Silver-Containing Titanium Dioxide Thin Films. Nanoscale Research Letters, 2009, 4, 313-320.	3.1	19
14	Bipolar pulsed electrical discharge for decomposition of organic compounds in water. Journal of Electrostatics, 2008, 66, 294-299.	1.0	76
15	Plasma Drift in Dual Magnetron Discharge. IEEE Transactions on Plasma Science, 2008, 36, 1412-1413.	0.6	15
16	Special type of plasma dielectric barrier discharge reactor for direct ozonization of water and degradation of organic pollution. Journal Physics D: Applied Physics, 2008, 41, 085207.	1.3	53
17	Bipolar Pulsed Electrical Discharges in Liquid. IEEE Transactions on Plasma Science, 2008, 36, 1156-1157.	0.6	11
18	Atmospheric plasma-calcination of mesoporous tungsten oxide utilizing plasma dielectric barrier discharge. Thin Solid Films, 2007, 515, 4905-4908.	0.8	5

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#	Article	IF	CITATIONS
19	Degradation of Bacteria Using Pulse Plasma Discharge in Liquid Medium. International Power Modulator Symposium and High-Voltage Workshop, 2006, , .	0.0	5
20	Magnetron Discharges for Thin Films Plasma Processing. , 2006, , 67-110.		14
21	Reactive magnetron sputtering of thin films: present status and trends. Thin Solid Films, 2005, 475, 208-218.	0.8	329
22	Reactive magnetron sputtering of TiOx films. Surface and Coatings Technology, 2005, 193, 107-111.	2.2	69
23	A study on the energy distribution for grid-assisting magnetron sputtering. Surface and Coatings Technology, 2005, 200, 421-424.	2.2	4
24	Discharge in dual magnetron sputtering system. IEEE Transactions on Plasma Science, 2005, 33, 338-339.	0.6	43
25	Magnetron with gas injection through hollow cathodes machined in sputtered target. Surface and Coatings Technology, 2001, 148, 296-304.	2.2	8